

Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE			ATTY. DOCKET NO. MI22-2497		SERIAL NO. 10/776,553	
<div style="position: relative; height: 100px;"> <div style="position: absolute; top: 0; left: 0; width: 100%; height: 100%; border: 1px solid black; border-radius: 50%; text-align: center; color: black; font-weight: bold; font-size: 1.2em;">             OIPE JUL 06 2005 PATENT &amp; TRADEMARK OFFICE           </div> </div>					LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)			
					APPLICANT Weimin Li et al.			
					FILING DATE February 10, 2004		GROUP 1755	
U.S. PATENT DOCUMENTS								
*Examiner Initial	AA	Document Number	Date	Name	Class	Sub-class	Filing Date If Appropriate	
<div style="font-size: 2em; font-weight: bold;">Q</div>	AB	6,503,818 B1	01-2003	Jang				
	AC	6,486,061 B1	11-2002	Xia et al.				
	AD	6,486,057 B1	11-2002	Yeh et al.				
	AE	6,465,372 B1	10-2002	Xia et al.				
	AF	6,444,593 B1	09-2002	Ngo et al.				
	AG	6,436,808 B1	08-2002	Ngo +.				
	AH	6,435,943 B1	08-2002	Chang +.				
	AI	6,429,115 B1	08-2002	Tsai +.				
	AJ	6,284,677 B1	09-2001	Hsiao +.				
	AK	6,030,901	02-2000	Hopper +.				
		6,133,618	10-2000	Steiner				
FOREIGN PATENT DOCUMENTS								
		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
<div style="font-size: 2em; font-weight: bold;">Q</div>	AN	0 942330	9/99	EPO				
	AO	6-244172	09/94	Japan			X	
	AP	200068261A	03-2000	Japan				
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)								
<div style="font-size: 2em; font-weight: bold;">Q</div>	AR	Beekman, K. et al., "Sub-Micron Gap Fill and In-Situ Planarisation Using Flowfill™ Technology", ULSI Conf., Portland, OR, Oct. 1995, pp. 1-7.						
<div style="font-size: 2em; font-weight: bold;">Q</div>	AS	Kiermasz, A. et al., "Planarisation for Sub-Micron Devices Utilising a New Chemistry", DUMIC Conf., California, Feb. 1995, pp. 1-2.						
<div style="font-size: 2em; font-weight: bold;">Q</div>	AT	Ralls, K. et al., "Introduction to Materials Science and Engineering", 1976 John Wiley & Sons, Inc., pp. 312-313.						
EXAMINER				DATE CONSIDERED				
<div style="font-size: 2em; font-weight: bold;">Q</div>				8/23/05				
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U.S. PATENT DOCUMENTS								
*Examiner Initial	Document Number	Date	Name	Class	Sub-class	Filing Date If Appropriate		
A	AA	5,994,217	11-1999	Ng	—			
	AB	5,991,217	11-1999	Tavrow et al.	—			
	AC	5,985,519	11-1999	Kakamu et al.	—			
	AD	5,747,388	05-1998	Küstors et al.	—			
	AE	5,639,687	06-1997	Roman et al.	—			
	AF	5,498,555	03-1996	Lin	—			
	AG	6,498,084B2	12-2002	Bergemont	—			
	AH	5,036,383	07-1991	Mori	—			
	AI	6,638,875	10-2003	Han et al.	—			
	AJ	6,720,247	04-2004	Kirkpatrick et al.	—			
	AK	6,723,631	04-2004	Noguchi et al.	—			
	AL	5,593,741	01-1997	Ikeda	—			
FOREIGN PATENT DOCUMENTS								
	Document Number	Date	Country	Class	Subclass	Translation		
						Yes	No	
A	AM	0 471185 A2	02/92	EPO	—			
C	AN	0 464515 A3	01/92	EPO	—			
G	AO	0 771886 A1	05/97	EPO	—			
B	AP	08-213386A	08-1996	Japan	—			
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)								
C	AR	Wolf, "Silicon Processing for the VLSI Era, Vol. 2: Process Integration," © 1990, pp. 189-190.						
C	AS	Wolf et al., "Silicon Processing for the VLSI Era - Vol. 1 - Process Technology," Prologue, page xxiii (2 pages total).						
C	AT	Heavens, O.S., "Optical Properties of Thin Solid Films", pp. 48-49.						
EXAMINER <i>R</i>				DATE CONSIDERED <i>8/23/05</i>				
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C	AA	6,121,133	09-2000	Iyer et al.			
	AB	2002/0016085	02-2002	Huang et al.			
	AC	2003/0164354	09-2003	Hsieh et al.			
	AD	2003/0173671	09-2003	Hironaga et al.			
	AE	2004/0175933	09-2004	Shishida et al.			
	AF	2004/0126671	07-2004	Smith et al.			
	AG	6,348,407	02-2002	Gupta et al.			
	AH	6,790,778	09-2004	Cheng et al.			
	AI	6,632,712B1	10-2003	Ang et al.			
	AJ	5,711,987	01-1998	Bearinger et al.			
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							Yes      No
C	AM	0 588087 A2/3	03-1994	EPO			
C	AN	9 055351	02-1997	JP			
C	AO	429473A	04-2001	TW			
C	AP	420844A	02-2001	TW			
C	AQ	368687A	09-1999	TW			
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
C	AR	Jenkins, F. et al., "Fundamentals of Optics", Properties of Light, pp. 9-10.					
C	AS	Dammel, R.R. et al., "Dependence of Optical Constants of AZ® BARLi™ Bottom Coating on Back Conditions, SPIE Vol. 3049 (1997), pp. 963-973.					
C	AT	Bencher, C. et al., "Dielectric Antireflective Coatings for DUV Lithography", Solid State Technology (March 1997), pp. 109-114.					
C	AU	Grant, J., "Hackh's Chemical Dictionary", McGraw-Hill, Inc. 1969, Fourth Edition, page 27.					
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FOREIGN PATENT DOCUMENTS							
		Document Number	Date	Country	Class	Subclass	Translation
							Yes    No
C	AK	0 778496 A2	05/96	EPO	—		
C	AL	06 067019A	03/94	JP (abstract)	—		
C	AM	1172845 A2	01-2002	EPO	—		
	AN						
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
C	AO	Anonymous, "New Gas Helps Make Faster ICs", Machine Design, Vol. 71, Iss. 21, Nov. 4, 1999, p. 118.					
4	AP	McKenzie, D.R. et al., "New Technology for PACVD", Surface and Coatings Technology, Vol. 82, pp. 326-333 (1996).					
C	AQ	Shibata, N., "Plasma-Chemical Vapor-Deposited Silicon Oxide/Silicon Oxynitride Double-Layer Antireflective Coating for Solar Cells", Jap. Jour. of App. Physics, Vol. 30, No. 5, May 1991, pp. 997-1001.					
	AR						
EXAMINER				DATE CONSIDERED <u>8/23/04</u>			
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